(12)

EUROPEAN PATENT APPLICATION

21 Application number: 90101754.1

(a) Int. Cl.5: C30B 33/00, C30B 29/06

2 Date of filing: 29.01.90

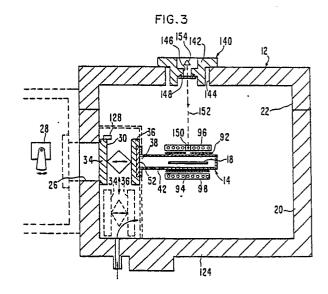
(30) Priority: 15.02.89 US 311686

Date of publication of application: 12.09.90 Bulletin 90/37

Designated Contracting States:
DE FR GB NL

Date of deferred publication of the search report: 05.12.90 Bulletin 90/49

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- (S4) Apparatus and method for processing a semiconductor wafer.
- (57) An apparatus and method for growing semiconductor quality oxide thermal layers on semiconductor wafers fast enough to be economically feasible as a single wafer process system. Process speed is insured by high pressure and high temperature. For example, if the pressure is about 100 atmospheres (1,500 psi) and at a temperature of 900°C, approximately 2.66 minutes are required to grow a 5,000Å oxide layer in a steam environment. The system can reach these operating conditions from ambient in approximately 30 seconds and depressurization and cool down require approximately 60 to 90 seconds. The apparatus includes a processing chamber to be pressurized with an oxidant, such as high pressure steam. The process chamber is contained in a pressure vessel adapted to be pressurized with an inert gas, such as nitrogen, to a high pressure. A pressure equalizing scheme is used to keep the fluid pressure of the process chamber and the pressure of the fluid pressure vessel substantially the same. The presdefining the process chamber. sure equalization permits the use of thin walls for





EUROPEAN SEARCH REPORT

EP 90 10 1754

				EP 90 10 17:
	DOCUMENTS CONSID	ERED TO BE RELEV	ANT	
Category	Citation of document with indic of relevant passa	cation, where appropriate, ges	Relevant to claim	CLASSIFICATION OF THE APPLICATION (Int. Cl.5)
Y	EP-A-0 062 174 (IBM * Page 1, lines 1-4; 19-29; page 4, lines	CORP.) page 2, lines	1-3,11- 13,21, 23,24, 27	C 30 B 33/00 C 30 B 29/06
Y	US-A-4 546 726 (NAGA * Figure 2; column 2,	NSAKI) lines 3-49 *	1-3,11- 13,21, 23,24, 27	
Y	US-A-4 154 192 (TSUE * Claims 1,2 *	BOUCHI et al.)	1-3,11- 13,21, 23,24, 27	
Α	EP-A-0 182 681 (BUE)	/OZ)		
A,D	US-A-4 315 479 (TOO! * Claims 1-3 *	_E et al.)	1,23	
A	FR-A-2 382 931 (ATO	MEL CORP.) t. D)		TECHNICAL FIELDS SEARCHED (Int. Cl.5)
A	US-A-4 253 417 (VAL) * Claim 1 *	ENTIJN)	1	C 30 B C 23 C H 01 L
A	US-A-4 018 184 (NAG	ASAWA et al.)		
		:	,	
	The present search report has be	en-drawn up for all claims		
	Place of search	Date of completion of the sea	į.	Examiner
TH	HE HAGUE	23-05-1990	C00	K S.D.
Y:p d A:te O:n	CATEGORY OF CITED DOCUMEN articularly relevant if taken alone articularly relevant if combined with anotocument of the same category echnological background non-written disclosure attermediate document	E: earlier p: after the D: documen L: documen	of the same patent fam	n



CLAIMS INCURRING FEES				
The present European patent application comprised at the time of filing more than ten claims.				
	All claims fees have been paid within the prescribed time limit. The present European search report has been drawn up for all claims.			
	Only part of the claims fees have been paid within the prescribed time limit. The present European search report has been drawn up for the first ten claims and for those claims for which claims fees have been paid.			
-	namely claims:			
	No claims fees have been paid within the prescribed time limit. The present European search report has been drawn up for the first ten claims.			
X LA	CK OF UNITY OF INVENTION			
The Search	Division considers that the present European patent application does not comply with the requirement of unity of and relates to several inventions or groups of inventions,			
namely:				
1.	Claims 1-22: Apparatus for processing (oxidizing) semiconducting wafer.			
	Claims 23-33: Method for processing (oxidizing) semiconducting wafer.			
2.	Claims 34,35: Power device per se.			
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	All further search fees have been paid within the fixed time limit. The present European search report has been drawn up for all claims.			
	Only part of the further search fees have been paid within the fixed time limit. The present European search report has been drawn up for those parts of the European patent application which relate to the inventions in respect of which search fees have been paid.			
	namely claims:			
₹	None of the further search fees has been paid within the fixed time limit. The present European search report has been drawn up for those parts of the European patent application which relate to the invention first mentioned in the claims, $1-22,23-33$			
1	namely claims:			